

# EUROPEAN PATENT OFFICE

## Patent Abstracts of Japan

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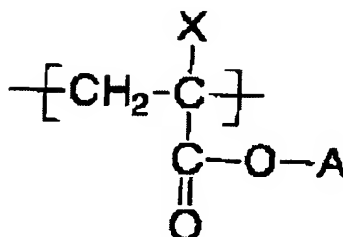
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APPLICANT : TORAY IND INC;

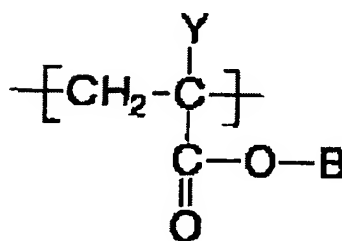
INVENTOR : SENOO MASAHIRO;

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C08F220/42 C08L 5/00 C08L 33/04  
C08L 33/18 H01L 21/027

TITLE : POSITIVE RADIATION-SENSITIVE  
COMPOSITION



(1)



(2)

ABSTRACT : PROBLEM TO BE SOLVED: To provide a positive radiation-sensitive composition having high sensitivity and sufficient resolution which enable pattern processing down to the order of subquarter micron possible.

SOLUTION: The positive radiation-sensitive composition contains a polymer, containing the structural units expressed by general formula (1) and general formula (2) and having the glass transition point T<sub>g</sub> of ≥80°C and ≤150°C, and an acid-generating agent which generates acid by irradiation of radiation. In formula (1), X is a 1-6C alkyl group, halogen element or cyano group, and A is a univalent organic group having tertiary carbon bonded to oxygen and containing an aromatic ring. In the formula (2), Y is a 1-6C alkyl group, halogen element or cyano group, and B is an alicyclic alkyl group.

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